



JP2001085395

Biblio

Page 1

Drawing



## SURFACE PROCESSING DEVICE

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### Abstract

**PROBLEM TO BE SOLVED:** To allow a stable element work in a broad process region by allowing the maximum output of a bias power source to be a high mode at pulse output while a low mode at continuous output, so that both the precision at low output and that at high output are provided, which is a problem related to pulsation of the bias power source.

**SOLUTION:** A bias power source 109 is provided with a pulse signal generator 110 for on/off control of it. The maximum output of the bias power source 109 is switched between a low mode and a high mode. At main etching, a bias power is pulse-modulated so that the bias power source 190 is made into the high mode. At over-etching, the bias power is continuous and the bias power source 109 is switched to the low mode. These modes are automatically switched. Thus, the precision at low output and that at high output are both provided, which is a problem related to pulsation of the bias power source 109.

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